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Form 1449 (Modified)

Information Disclosure Statement By Applicant

(Use Several Sheets if Necessary)

Atty Docket No.
NOVLP096/NVLS-2902

Application No.:
10/815,560

Applicant:
Wongsenakhum et al.

Filing Date
March 31, 2004

Group
2823

U.S. Patent Documents

Foreign Patent or Published Foreign Patent Application

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
<i>MP</i>	C1	Chan et al., "Methods for Growing Low-Resistivity Tungsten Film", Novellus Systems, Inc., filed November 1, 2005, Application No. 11/265,531, pages 1-35. [NOVLP137/NVLS-0003093]
<i>MP</i>	C2	Levy et al., "Deposition of Tungsten Nitride", Novellus Systems, Inc., filed December 16, 2005, Application No. 11/305,368, pages 1-39. [NOVLP063D1/NVLS-2615D1].
<i>MP</i>	C3	U.S. Office Action mailed December 28, 2005, from U.S. Application No. 10/649,351 [NOVLP033X1/NVLS-000498X1].
Examiner	<i>Michele Piatada</i>	
	Date Considered	
	<i>3/3/06</i>	

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



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